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(54) Title: THERMALLY REACTIVE NEAR INFRARED ABSORPTION POLYMER COATINGS, METHOD OF PREPARING AND METHODS OF USE

(57) Abstract

Provided herein are novel polymeric coating materials for direct digital imaging by laser. More specifically the novel coating materials are thermally reactive near infrared absorption polymers designed for use with near infrared laser imaging devices. This invention further extends to the preparation and methods of use of the novel materials. The invention is particularly useful in the preparation of lithographic printing plates for computer–to–plate and digital–offset–press technologies. The invention extends to photoresist applications, to rapid prototyping of printed circuit boards and to chemical sensor development.